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## (54) SILOXANE POLYMER AND RESIST COMPOSITION

(57)Abstract:

**PURPOSE:** To obtain a higher glass transition temp. and to improve oxygen plasma resistance by protecting a part or the whole of the hydroxyl group of specific polysiloxane with an alkyl group, substd. alkyl group, arom. group or silyl group.

**CONSTITUTION:** The chemical structure of a ladder type which adopts the siloxane bond as a skeletal structure and uses the multifunctional alkoxysilane as a raw material is adopted in such a manner and the hydroxyl group subjected to ring opening by the introduction of the oxysilane ring is protected by the suitable functional groups, by which alkaline development is enabled. The higher glass transition temp. is obtd. in this way and the oxygen plasma resistance is improved.

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## LEGAL STATUS

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